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(54) Title (EN): ANTI-REFLECTIVE FILM AND PRODUCTION METHOD FOR SAME

(54) Title (FR): FILM ANTIREFLET ET SON PROCÉDÉ DE PRODUCTION

(54) Title (JA): 反射防止フィルムおよびその製造方法

(57) Abstract:

(EN): Provided are: an anti-reflective film that achieves both transparency and finger glide; and a production method for the anti-reflective film. An anti-reflective film 10 that has a base material film 12 and a first resin layer 14 that is formed on the surface of the base material film 12. The first resin layer 14 includes large diameter particles 18 that form protrusions at the surface of the first resin layer 14, hollow silica particles 22 that have a smaller average particle diameter than the large diameter particles 18, and a binder resin. The large diameter particles 18 are preferably 1.0-3.5 mass% of the content of the first resin layer 14, and the hollow silica particles 22 are preferably 30-70 mass% of the content of the first resin layer 14.

(FR): L'invention concerne : un film antireflet qui permet d'obtenir à la fois la transparence et le glissement du doigt ; et un procédé de production du film antireflet. Un film antireflet (10) selon l'invention comprend un film de matériau de base (12) et une première couche de résine (14) qui est formée sur la surface du film de matériau de base (12). La première couche de résine (14) comprend des particules de grand diamètre (18) qui forment des saillies à la surface de la première couche de résine (14), des particules de silice creuses (22) qui ont un diamètre de particule moyen plus petit que les particules de grand diamètre (18), et une résine liante. Les particules de grand diamètre (18) représentent de préférence de 1,0 à 3,5 % en masse du contenu de la première couche de résine (14), et les particules de silice creuses (22) représentent de préférence de 30 à 70 % en masse du contenu de la première couche de résine (14).

(JA): 指滑り性と透明性を両立できる反射防止フィルムおよびその製造方法を提供する。　基材フィルム１２と、基材フィルム１２の面上に形成された第一樹脂層１４と、を有し、第一樹脂層１４が、第一樹脂層１４の表面に凸部を形成する大径粒子１８と、大径粒子１８よりも平均粒子径の小さい中空シリカ粒子２２と、バインダー樹脂と、を含む反射防止フィルム１０とする。大径粒子１８の含有量は、第一樹脂層１４の全量基準で、１.０～３.５質量％の範囲内であり、中空シリカ粒子２２の含有量は、第一樹脂層１４の全量基準で、３０～７０質量％の範囲内であることが好ましい。

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